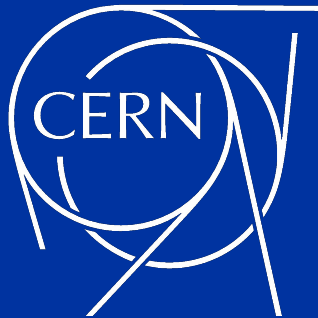


7th November 2025



university of
 groningen



Simulation and Characterization of fast and radiation hard 3D silicon sensors

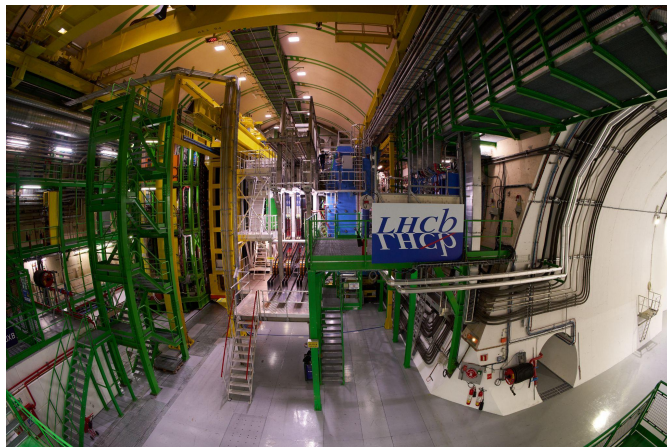
Alfonso Puicercus Gomez

on behalf of EP R&D WP1.1 at CERN and University of Groningen

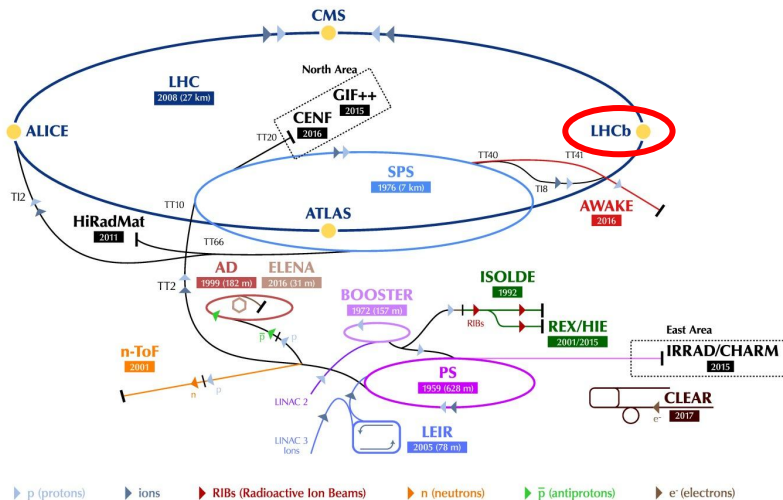
Motivation

LHCb Upgrade II

- CERN hosts the Large Hadron Collider (LHC)
- LHCb is one of the four main experiments
 - optimized for the study of heavy flavour physics and CP violation in the b- and c-quark sectors
 - Located in the forward region, LHCb operates under high particle multiplicities, requiring precise tracking and fast readout.



The CERN accelerator complex
Complexe des accélérateurs du CERN

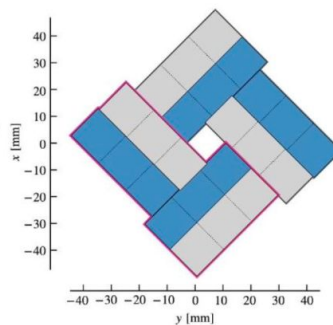
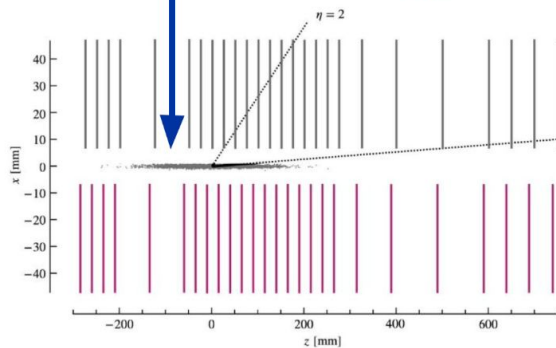
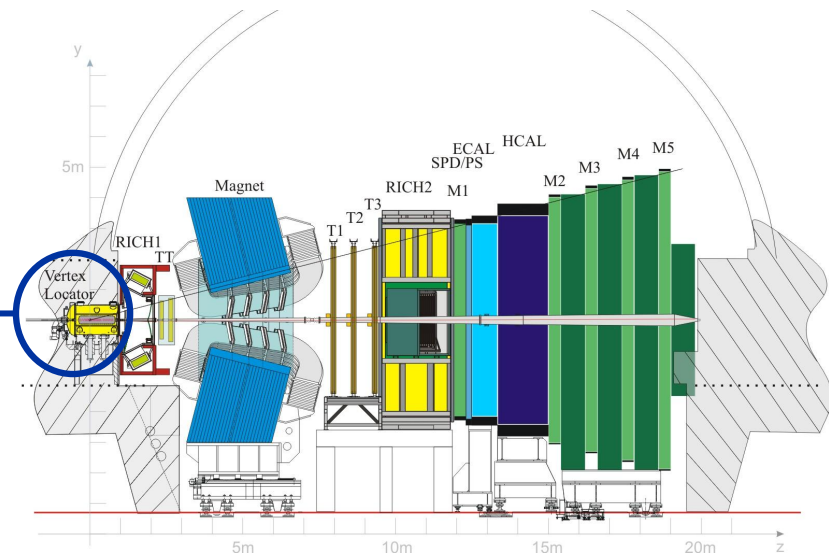
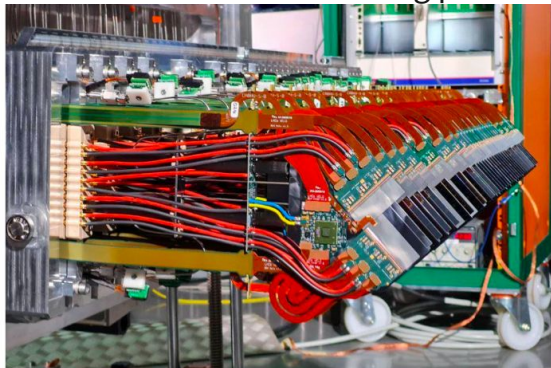


LHC - Large Hadron Collider // SPS - Super Proton Synchrotron // PS - Proton Synchrotron // AD - Antiproton Decelerator // CLEAR - CERN Linear Electron Accelerator for Research // AWAKE - Advanced WAKEfield Experiment // ISOLDE - Isotope Separator OnLine // REX/HIE - Radioactive EXperiment/High Intensity and Energy ISOLDE // LEIR - Low Energy Ion Ring // LINAC - LINear ACcelerator // n-ToF - Neutrons Time Of Flight // HiRadMat - High-Radiation to Materials // CHARM - Cern High energy AccelERator Mixed field facility // IRRAD - proton IRRAdiation facility // GIF++ - Gamma Irradiation Facility // CENF - CERN Neutrino platform

Motivation

LHCb Upgrade II

- The **VELO (Vertex Locator)** is LHCb's innermost tracking subdetector:
 - Positioned millimetres from the proton beams.
 - Provides primary and secondary vertex reconstruction with micrometre precision
- **Current VELO technology approaching limits:**
 - **Readout hybrid:** Existing electronics challenged by extreme particle fluxes.
 - **Planar sensors:** Standard sensor designs nearing radiation tolerance and timing performance limits.



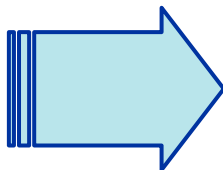
Motivation

MIP detection in next generation of collider experiments

from the CERN Strategic R&D Programme on Technologies for Future Experiments [CERN-OPEN-2018-006]

[fineprint in CERN-OPEN-2018-006]	HL-LHC	SPS	FCC-ee	FCC-hh
Total fluence [$n_{\text{eq}} \text{ cm}^{-2} \text{ s}^{-1}$]	5×10^{16}	10^{17}	10^{10}	10^{17}
Max Hit rate [$\text{cm}^{-2} \text{ s}^{-1}$]	2-4G	8G	20M	20G
Material budget per layer [X_0]	0.1-2%	2%	0.3%	1%
Pixel size [μm^2] inner trackers	50x50	50x50	25x25	25x25
Temporal hit resolution [ps] inner trackers	~50	~40	-	~10

- Time resolution 10 - 50 ps
- Pixel pitches down to 25 μm
- Fluences up to $10^{17} n_{\text{eq}}/\text{cm}^2/\text{y}$
- Max hit rate up to 20 G/cm²/s

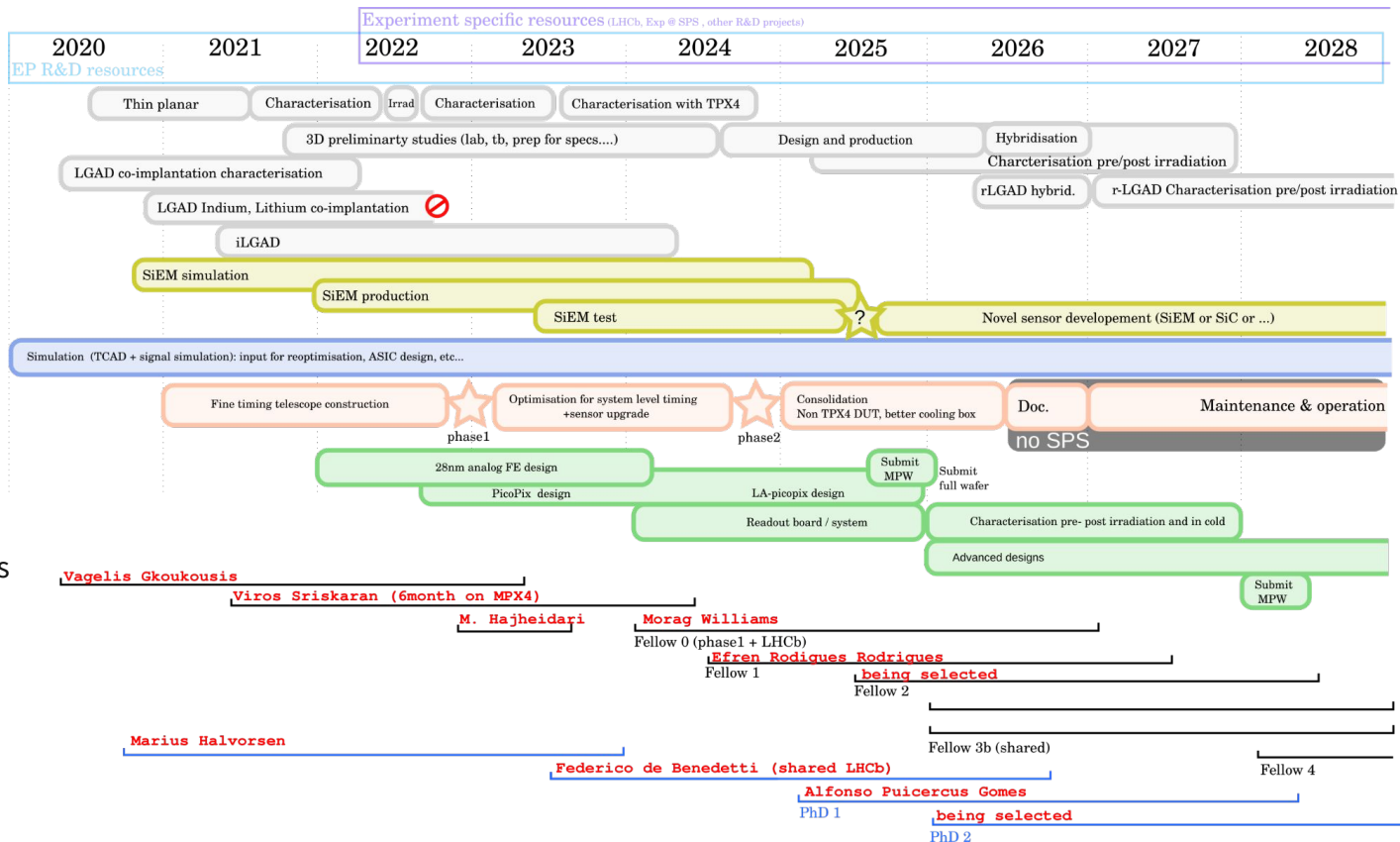


Challenges for sensor
Challenges for front-end electronics

Motivation

Timeline

- **Sensor development:**
 - Fast 3D and SiEM
- **Simulation and characterisation:**
 - TPX4 telescope, OPTIMA, TCT setup and IV/CV
- **Readout:**
 - from picopix to LA-picopix and its readout



3D sensors

Fundamentals

- **How silicon sensors work:**

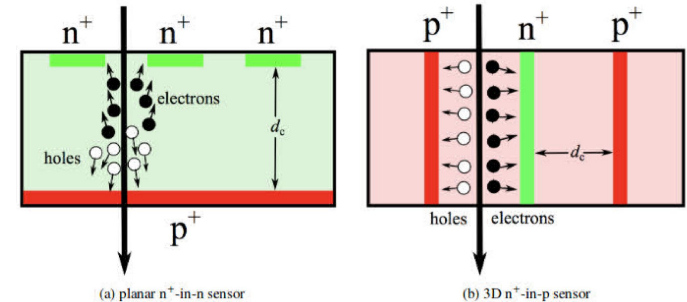
- A silicon detector measures charged particles by collecting electron-hole pairs created when a particle crosses the silicon.
- An electric field across a depleted region drifts these charges to electrodes → producing a measurable signal.

- **Planar sensors:**

- Electrodes on opposite surfaces
- E field across full thickness → charge travels through the entire bulk.
- ☒ Mature tech, simple fabrication.
- ☒ Slow charge collection (long drift distance).
- ☒ High depletion voltage, especially after radiation damage.

- **3D sensors:**

- Electrodes are vertical columns etched into the silicon
- E field between columns
- ☒ Shorter drift distance → faster collection.
- ☒ Low depletion voltage & radiation hardness.
- ☒ More complex fabrication, smaller active volume per pixel.



Saleem, 2019 (PhD thesis)

3D sensors

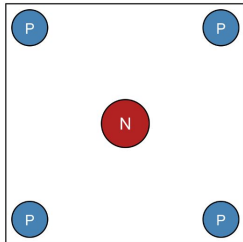
Fundamentals

- **Main parameters of interest in 3Ds:**

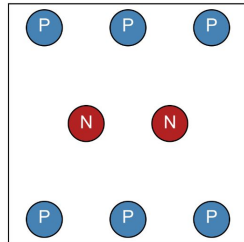
- General Geometry on columns (1E, 3:2:3, Hex)
- Fabrication process (Double vs Single Sided)
- Thickness of bulk
- Column diameter
- Column gaps
- Doping profiles
- Isolation structures

Three Sensor Geometries

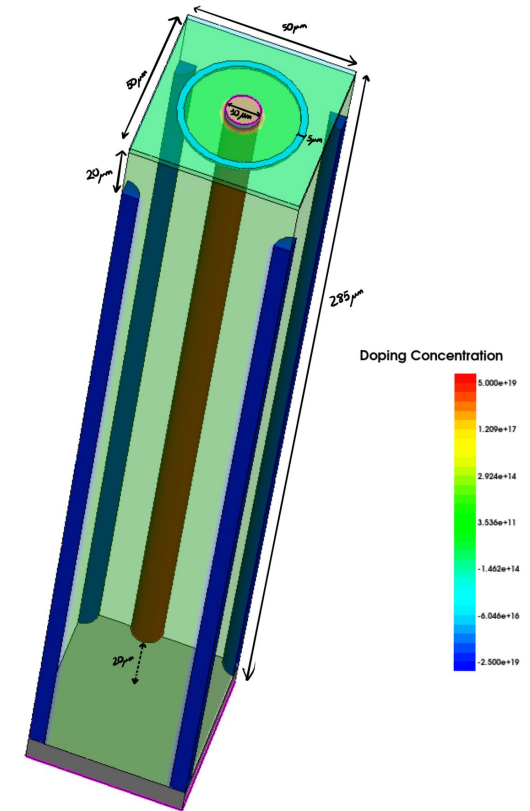
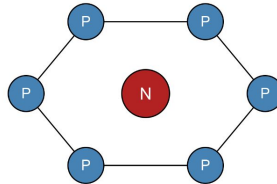
1E Geometry



3-2-3 Geometry



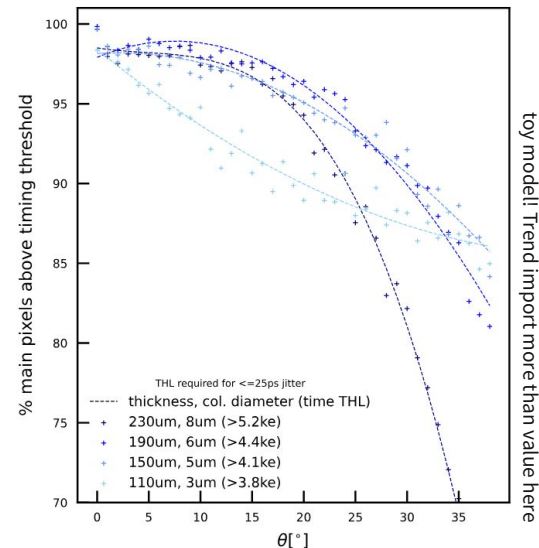
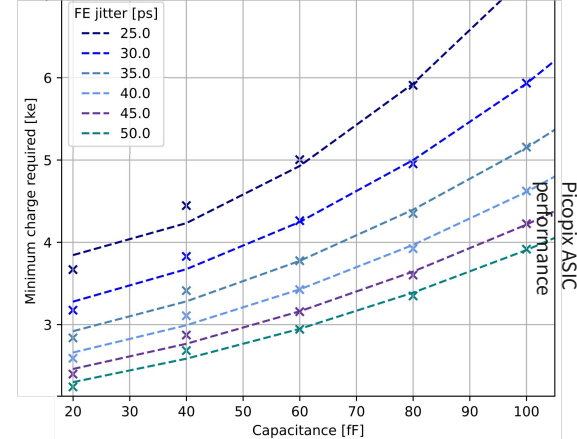
Hexagonal Geometry



3D sensors

Timing-Driven Sensor Design Considerations

- **Timing resolution depends on:**
 - Collected charge (signal strength)
 - Sensor capacitance (rise time, noise)
- **Design optimizations:**
 - Increase bulk thickness → more charge, reduced timewalk correction
 - Reduce column diameter → lower capacitance
⇒ **High AR columns required → fabrication challenge**
- **Larger thickness remains favourable on two fronts:**
 - higher charge reduces the error correction on the intrinsic time resolution
 - lower angle needed for optimal charge sharing (easier to design a detector)
⇒ **thickness to be investigated**
- **Investigate various column geometries:**
 - 1E, 2E, 3:2:3, hex, 50x50 (and 25x100 to be checked in simu)
- Have **large structures** available to bond to Picopix and TPX4 ASICs

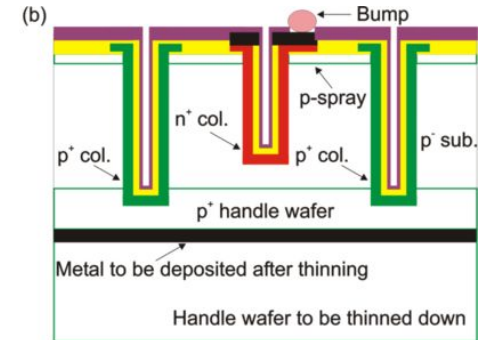
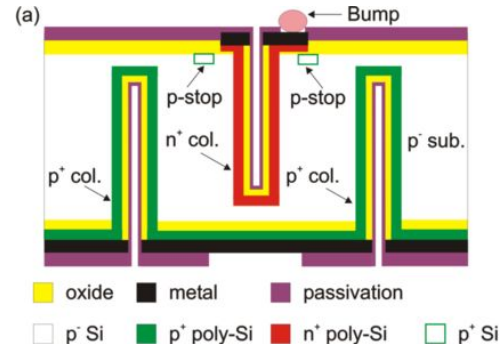
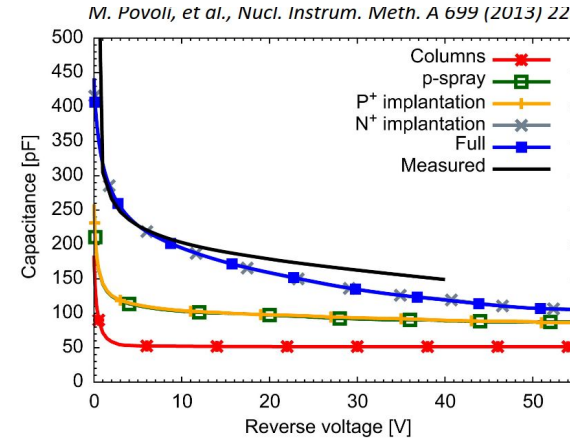


3D sensors

Fabrication Design Considerations

- **Double sided (DS)(a) vs Single/One sided (OS)(b)**
 - ⇒ **study into choice of fabrication process**
 - possible pass-through columns for better homogeneity in response and high voltage, with a reduction in efficiency
- **Isolation structures:**
 - ***p-stop*** vs ***p-spray*** to improve HV tolerance and interpixel capacitance
 - ⇒ **dedicated R&D structures**

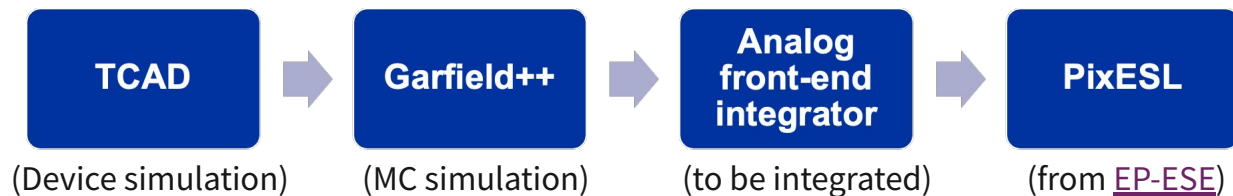
Designs and studies driven by simulation studies.



Simulations

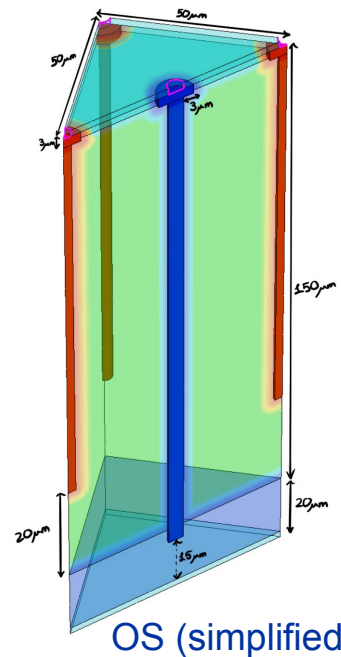
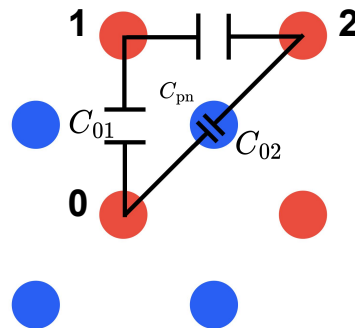
Overview

- Support from simulation to drive the parameter space
- Now using this understanding as the basis to perform focused, detailed simulations of different 3D sensor designs within a full workflow:



- **TCAD 3D models:**

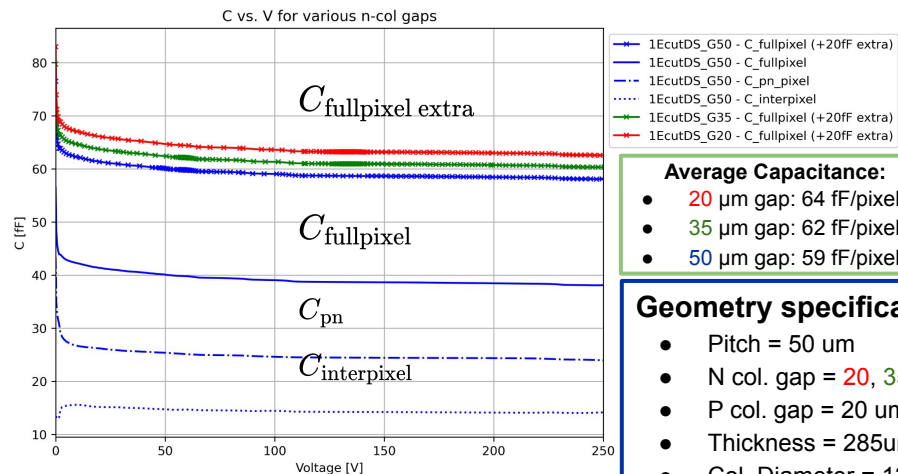
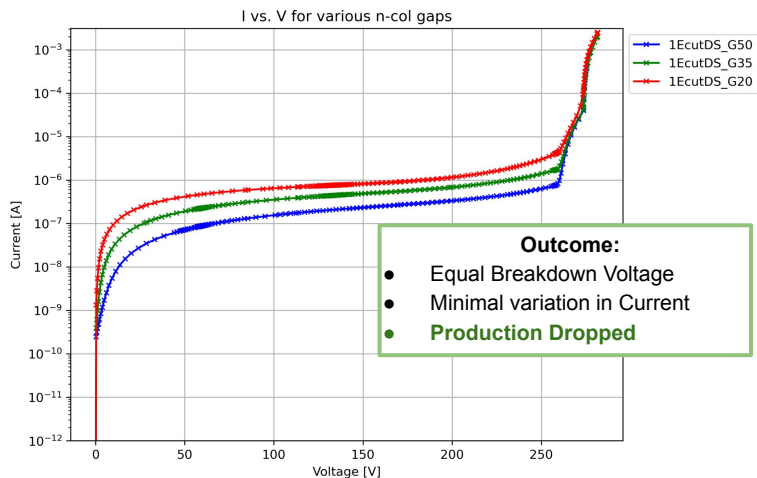
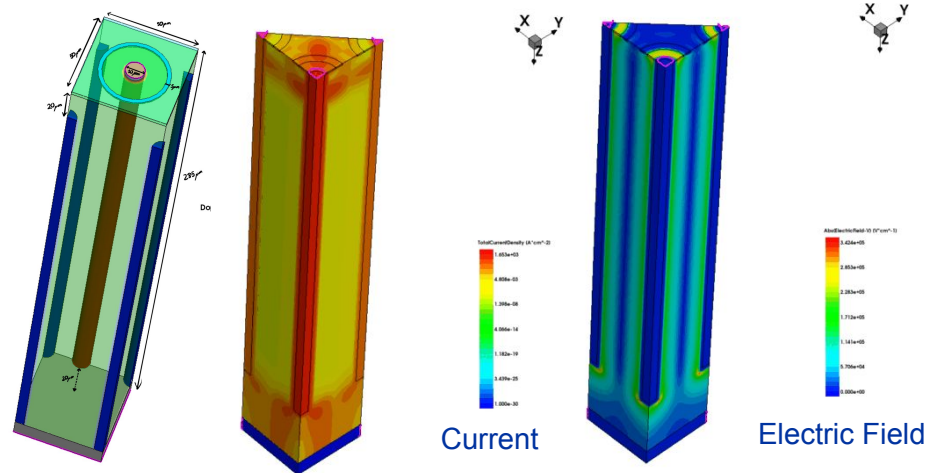
- Fully parametrized sensor design
- Simplified model:
 - reduced computational time
 - account for neighbouring readout electrodes



Simulations: TCAD

Double Sided: under n-column gap variation

- **Study:**
 - Multiple under n-column gaps considered
 - For further details see this [presentation](#)
- **Aim:**
 - Verify breakdown location within pixel
 - Study influence of shorter/larger n columns



Geometry specifications:

- Pitch = 50 μm
- N col. gap = 20, 35, 50 μm
- P col. gap = 20 μm
- Thickness = 285 μm
- Col. Diameter = 12 μm

Simulations: TCAD

One Sided: Isolation mechanisms

- **Study:**
 - **P-stop** vs **P-spray**
 - Influence of doping dosage
- **Aim:**
 - Determine benefits of each isolation mechanism

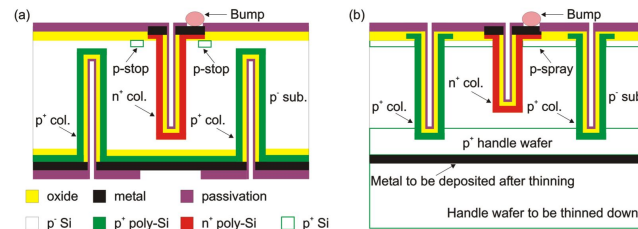
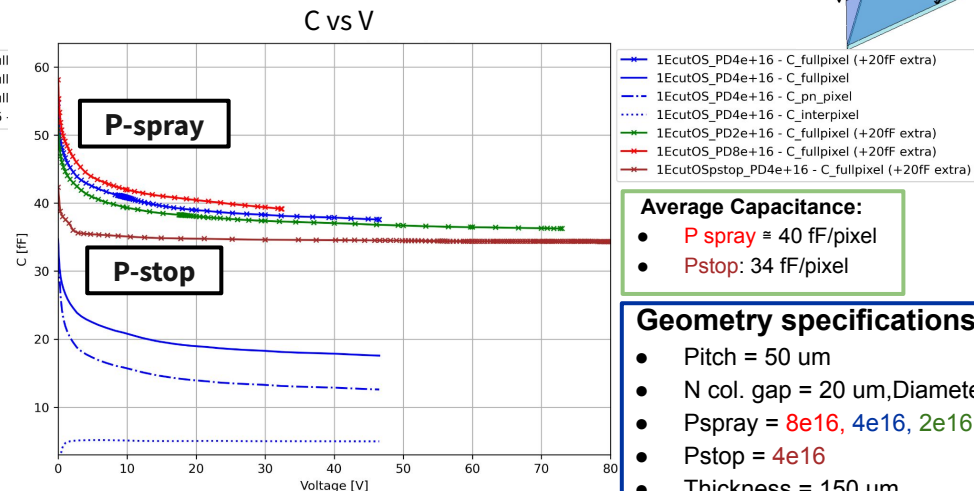
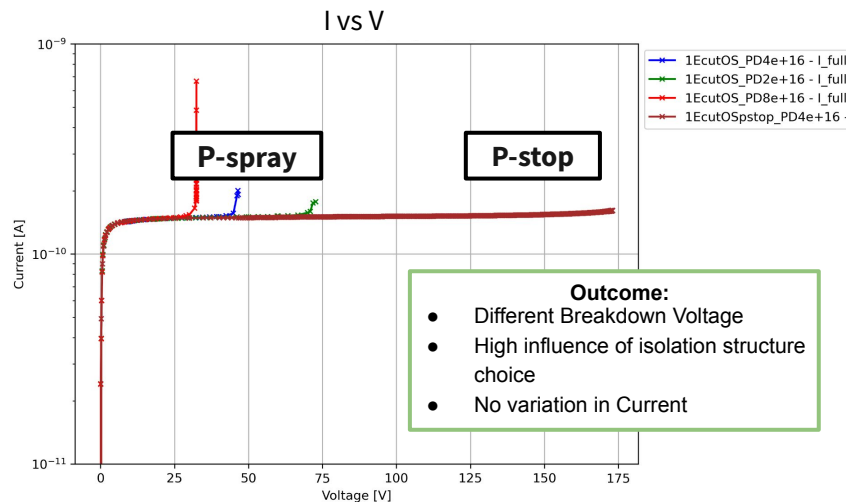
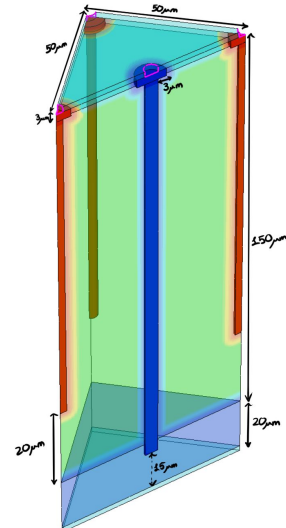


Figure 1 Schematic cross-sections of small pitch 3D sensors: (a) double-sided, and (b) single-sided.

[G.F. Dalla et al. PoS \(Vertex 2016\) 028](#)



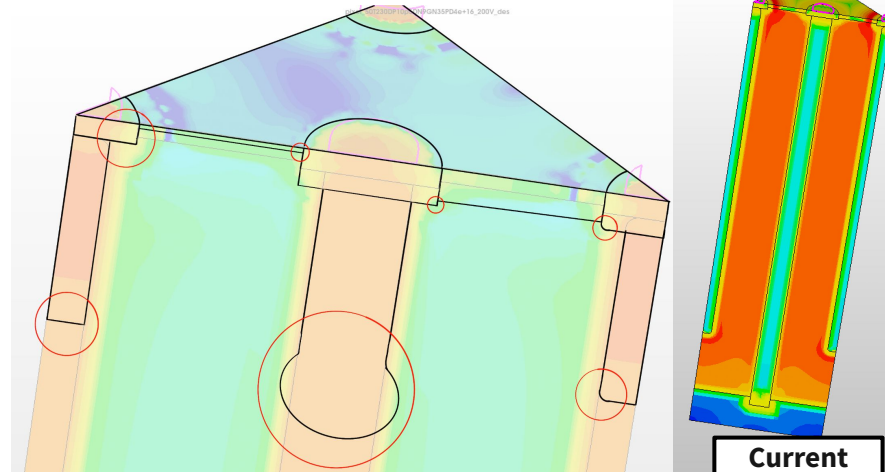
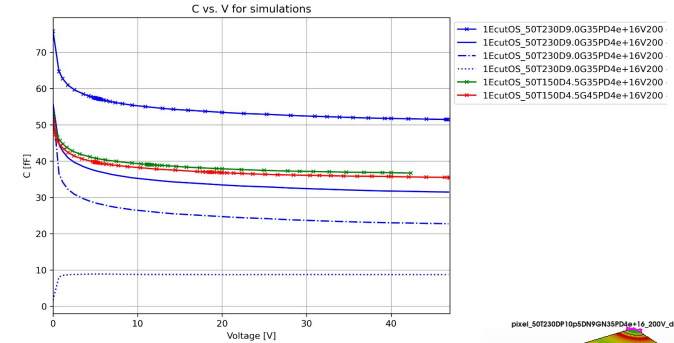
Simulations: Status and Plans

Simulation status:

- **Gap under n-columns variation:** No influence in breakdown voltage, similar current and capacitance. Breakdown most likely due to surface effects and gap of p-column (*Double Sided model*)
- **Isolation structures:** Higher breakdown voltage and lower capacitance with p-stop than p-spray. (*Single Sided model*)

Recent and upcoming studies:

- **Surface effects and isolation structures:** improvements seeking lower capacitance, pushing breakdown voltage...
- **Inform productions to meet expected sensor performance:** using feedback from SINTEF for model accuracy



Simulations: Status and Plans

Overall Simulation Pipeline

Further improvements:

- Custom GUI and mattermost bot for planned simulation chain: easy visualisation of simulation parameters, projects, status notifications...

```
<module>:DONE!  
<module>:-  
<module>:- Elapsed time: 0.01 hours  
<module>:-  
<module>:- Compile time: 0.53 seconds  
<module>:- Geometry time: 0.0 minutes  
<module>:- Simulate time: 0.0 hours  
<module>:- Weighting time: 0.0 hours  
<module>:- Garfield time: 0.0 hours  
<module>:- Plot time: 0.0 minutes  
<module>:- Svisual time: 0.34 minutes  
<module>:- Backup time: 0.0 minutes  
<module>:-  
run_simulations.py -p 1EcutOS -cmp -sv:
```

```
TCAD-Bot BOT 02:00  
@Alfonso Pulcercus Gomez - TCAD Simulate COMPLETED  
  
✓ SIMULATE Step COMPLETED  
Configuration: 1/4  
Structure: 50,0T230,0DP10,5DN9,0GP0,0GN35,0PR3,0PT1,0PD2e+16_200,0V  
Duration: 3.40 hours  
Pitch: 50.0  
Bulk Thickness: 230.0  
P Diameter: 10.5  
N Diameter: 9.0  
P Gap: 0.0  
N Gap: 35.0  
Pstop Thickness: 1.0  
Extra Radius: 3.0  
P Spray Doping: 2e+16  
Voltage: 200.0  
Completed: 2025-07-14 02:00:33
```

TCAD Simulation Tracker

Filters

Project: All pitch: All bulk_thickness: All p_diameter: All n_diameter: All
n_gap: All p_gap: All p_stop_doping: All pstop_thickness: All plusplus_extraradius: All
vbot: All Status: All Apply Filters Clear Filters

Simulation Controls

Select simulations from table, then click a step to run:

Compile	Geometry	Mesh
Simulate	Weight	Garfield
Plot	SVisual	Full

Simulation Data

Order	Project	pitch	bulk_thick	np_diam	n_diam	p_gap	n_gap	plusp	pstop	thicp	stop_dop	vbot	Status
70	1EcutOS	50	230	10.5	9.0	nan	35	nan	5.0	4e+16	200.0	IV/CV, Failed	
69	1EcutOS	50	230	10.5	9.0	nan	35	nan	3.0	4e+16	200.0	IV/CV, Failed	
68	1EcutOS	50	230	10.5	9.0	nan	35	nan	1.0	4e+16	200.0	IV/CV, Failed	
67	1EcutOSSINTEI	50	230	10.5	9.0	0.0	35	6.5	1.0	2e+16	200.0	Complete	
66	1EcutOSSINTEI	50	230	10.5	9.0	0.0	35	3.0	1.0	2e+16	200.0	Complete	
65	1EcutOSSINTEI	50	150	10.5	9.0	0.0	35	3.0	5.0	2e+16	200.0	IV/CV, not Qua	
64	1EcutOSSINTEI	50	150	10.5	9.0	0.0	35	3.0	4.5	2e+16	200.0	IV/CV, not Qua	
63	1EcutOSSINTEI	50	150	10.5	9.0	0.0	35	3.0	3.0	2e+16	200.0	IV/CV, not Qua	
62	1EcutOSSINTEI	50	150	10.5	9.0	0.0	35	3.0	2.0	2e+16	200.0	IV/CV, not Qua	
61	1EcutOSSINTEI	50	230	10.5	9.0	0.0	35	3.0	2.0	2e+16	200.0	IV/CV, not Qua	
60	1EcutOSSINTEI	50	230	10.5	9.0	0.0	35	3.0	1.0	2e+16	200.0	Failed	
59	1EcutOSSINTEI	50	230	10.5	9.0	0.0	35	5.5	1.0	2e+16	200.0	Complete	
58	1EcutOSSINTEI	50	230	10.5	9.0	0.0	35	4.0	1.0	2e+16	200.0	Complete	
57	1EcutOSSINTEI	50	230	10.5	9.0	0.0	35	6.5	1.0	2e+16	200.0	Failed	
56	1EcutOS	50	285	10.0	10.0	5.0	20	nan	1.0	4e+16	300.0	Quasi but no IV	
55	1EcutOSSINTEI	50	230	10.5	9.0	0.0	35	5.5	1.0	2e+16	200.0	Failed	
54	1EcutOSSINTEI	50	230	10.5	9.0	0.0	35	4.0	1.0	2e+16	200.0	Failed	
53	1EcutOS	50	285	10.0	10.0	25.0	20	nan	1.0	4e+16	300.0	Quasi but no IV	
52	1EcutOS	50	230	10.5	9.0	nan	35	nan	5.0	4e+16	200.0	Quasi but no IV	
51	1EcutOS	50	285	10.0	10.0	20.0	20	nan	1.0	4e+16	300.0	Quasi but no IV	
50	1EcutOS	50	230	10.5	9.0	nan	35	nan	3.0	4e+16	200.0	Quasi but no IV	
49	1EcutOS	50	230	10.5	9.0	nan	35	nan	1.0	4e+16	200.0	Quasi but no IV	
48	1EcutOS	50	230	10.5	9.0	nan	35	nan	nan	4e+16	200.0	Complete	
47	1EcutOS	50	230	10.5	9.0	nan	35	nan	nan	4e+16	202.0	Quasi but no IV	
46	1EcutOS	50	230	10.5	9.0	nan	35	nan	nan	4e+16	200.0	Failed	
45	1EcutOS	50	230	10.5	9.0	nan	35	nan	nan	4e+16	201.0	Quasi but no IV	
44	1EcutOS	50	230	10.5	9.0	nan	35	nan	nan	4e+16	201.0	Failed	
43	1EcutOS	50	150	6.0	4.5	nan	45	nan	nan	4e+16	200.0	Complete	
42	1EcutOS	50	150	6.0	4.5	nan	35	nan	nan	4e+16	200.0	Complete	
41	1EcutOS	50	150	7.0	5.0	nan	35	nan	nan	4e+16	200.0	Quasi but no IV	

Analysis Tools

Plot IV Plot CV Plot All

Capacitance Refresh Data

Simulation Summary

Complete: 27 Quasi but no IV/CV: 16 IV/CV, not Quasi: 8 IV/CV, Failed: 13 Failed: 6

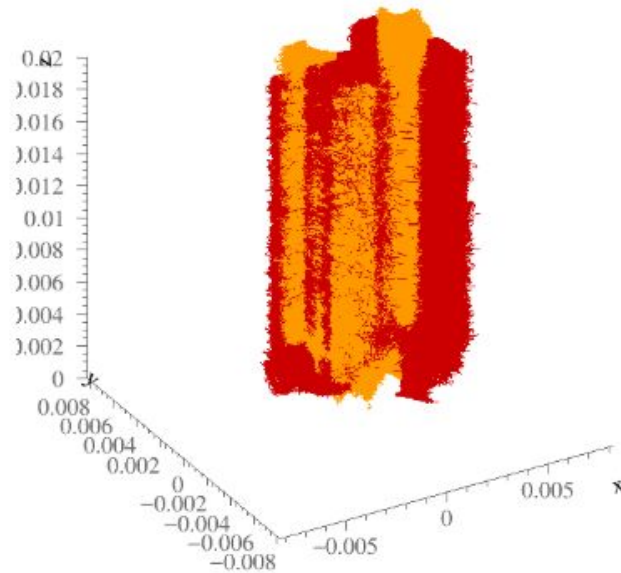
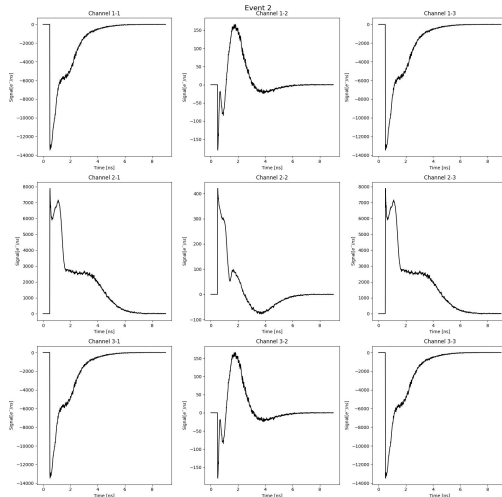
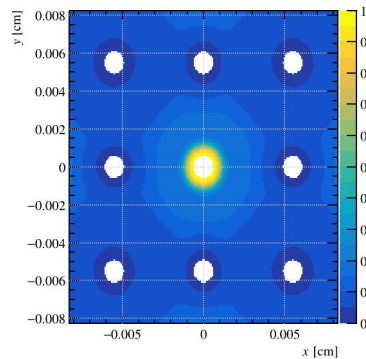
No simulations selected

Simulations: Status and Plans

Garfield++

Progress:

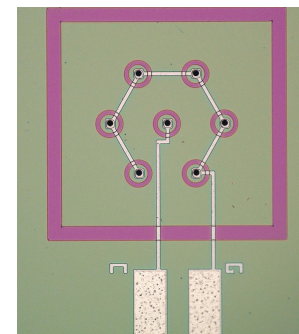
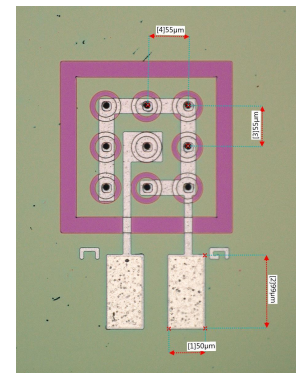
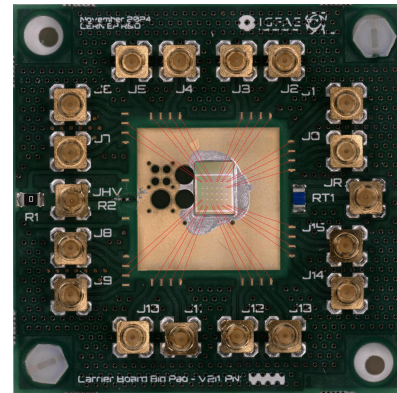
- Able to place tracks at chosen or random locations+angles
- Simulation scripts ready to be used
- Some improvements to be made on Garfield++ for complete usability and accuracy



Characterisation

Planning

- **Structures from RD50 CNM fast timing 3D**
 - Already studied by other group see [DRD3 Leena's talk](#)
 - Complement the study of the signal development and timing as function of track angle
 - To be used to validate the simulation pipeline, in particular Garfield++ response
- **Wire bonding done in some structures already.**
- **Test beam using the OPTIMA boards integrated to TPX4 telescope.**
- **Irradiation campaign completed last week. IVs and wirebonding to be done, together with inclusion in next testbeam**



Special thanks to CNM for providing valuable support with a 3D double-sided TCAD model and for producing the sensors currently under study in our lab.

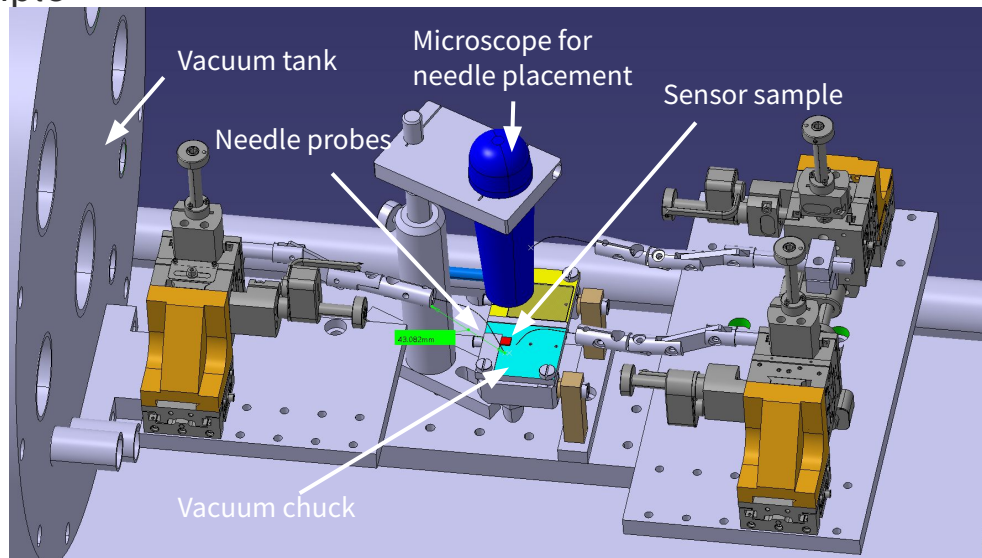
Characterisation

Setups

- **Within WP1.1, commissioning our own characterisation set-ups:** IV-CV, laser deposition, source measurements, OPTIMA / 16 channel board, test-beam telescope
- **Multiple of these set-ups exist at CERN** → idea is to **commission dedicated set-ups for the 100s of test structures** being produced within WP1.1 to **tailor characterisation process** to our needs and **optimise the time taken** per sample

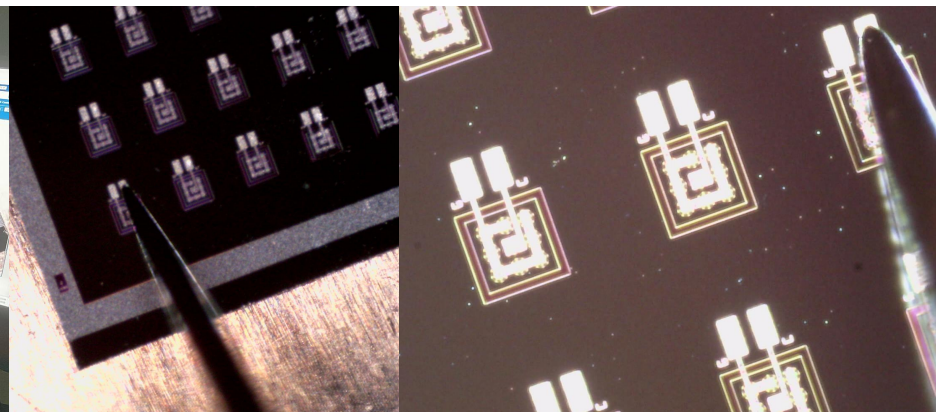
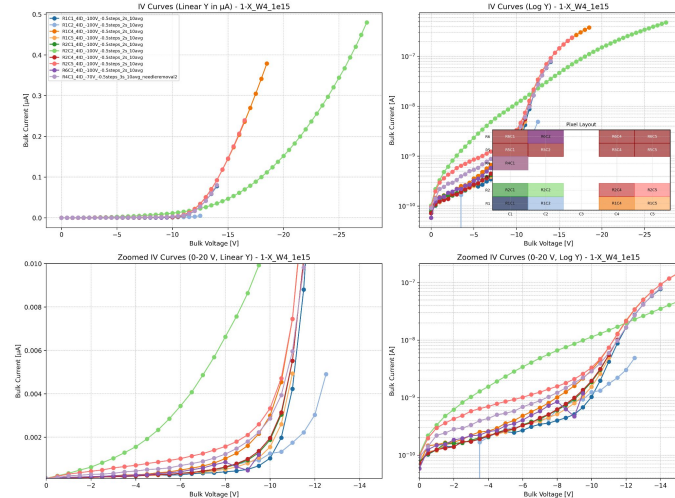
IV/CV set-up

- Needles on motion stages for fast sample replacement and reproducibility inside a controlled environment.



IV/CV set-up

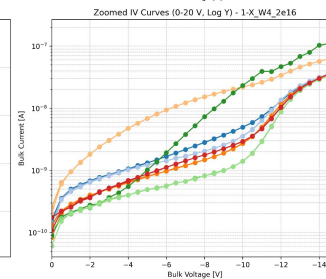
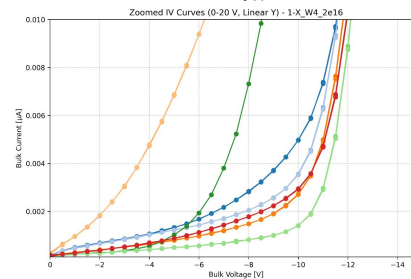
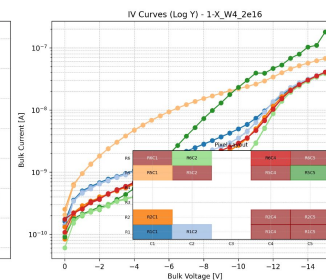
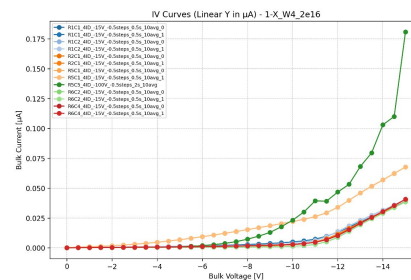
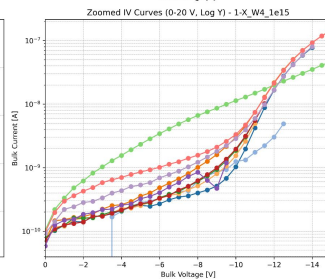
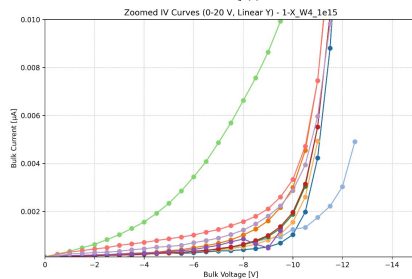
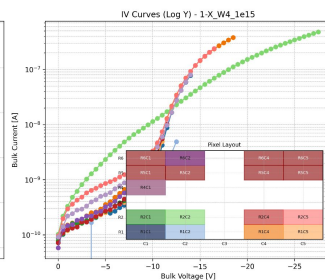
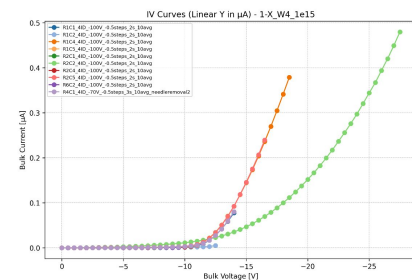
- **First IVs taken for samples sent to irradiation:**
 - Single pixels 1E and Hexagonal geometry
 - Interconnected pixel matrices 1E geometry
- **To be characterised post irradiation**
 - Setup being commissioned with cooling and monitoring



Characterisation

IV/CV set-up

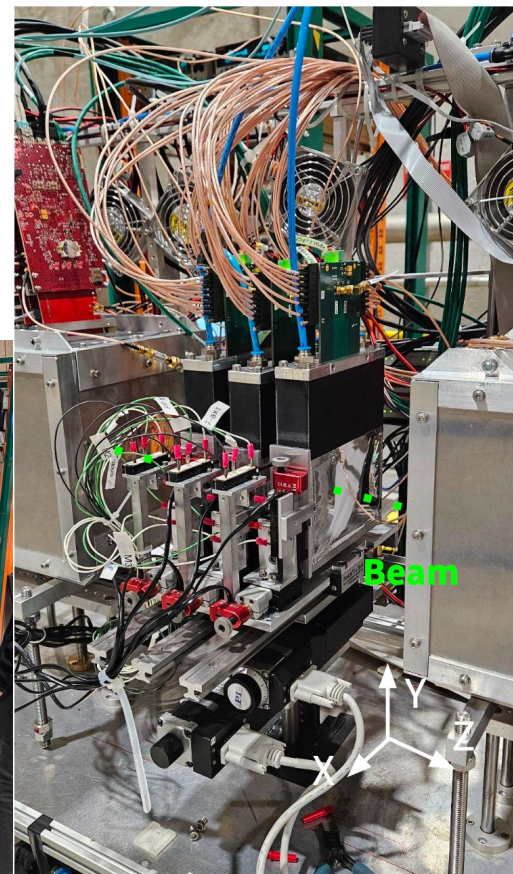
- **First IVs taken for samples sent to irradiation:**
 - Significant pixel-to-pixel variation in IVs
 - Likely due to bad production, other groups also observed such behaviour



Characterisation

Test Beam May, July, October 2025

- Test beam campaigns with Timepix4 telescope.
- Setup:
 - Optima Boards on back stage
 - PCBs with **Planar**, **3D**, **LGAD**, **SiEM** sensors
- Issues encountered:
 - Software: SAMPIC triggers and configuration
 - Hardware: Spatial and timing alignment
- Outcome:
 - Runs of data for 3D sensors for analysis:
 - Bias scan
 - Angle scan
 - To be analysed soon, aiming for:
 - Efficiency studies
 - Signal formation and shape vs angle

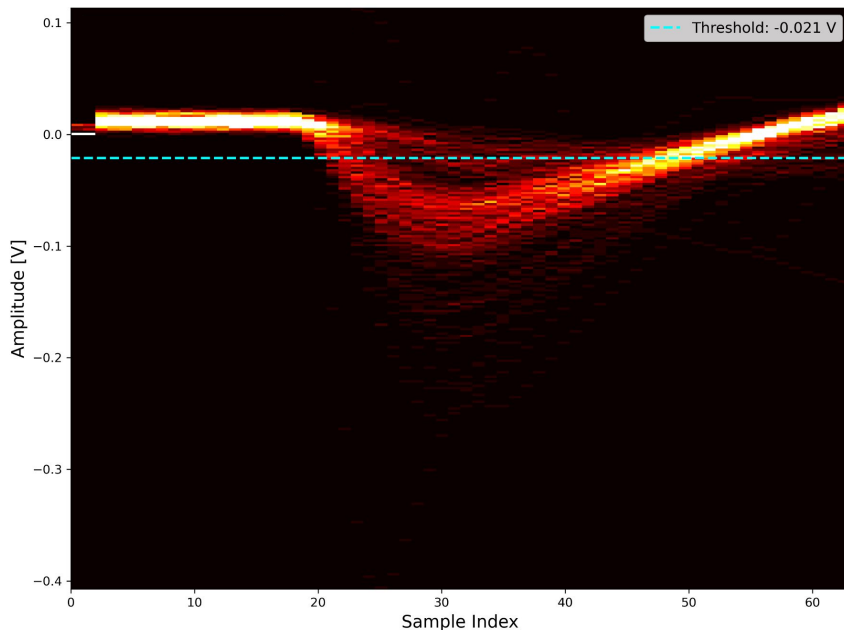


Characterisation

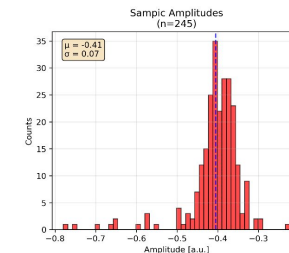
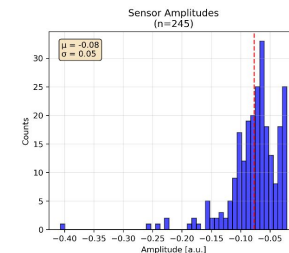
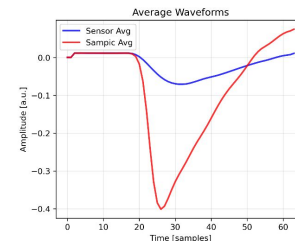
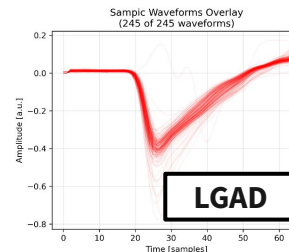
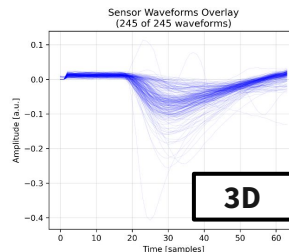
Test Beam July 2025

- Some early plots:

Sensor - 2D Grid Binning Analysis
Grid: 64×256 bins, Color = Count per Bin



Waveform Analysis
Run11300 Sampic Ch: 20 (th=-0.2), Sensor Ch: 27 (th=-0.02111)



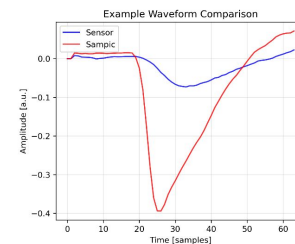
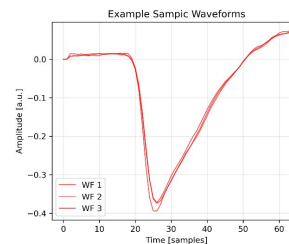
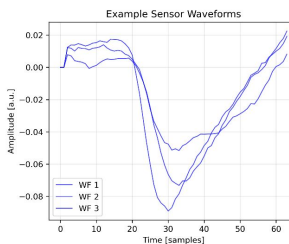
Analysis Summary

Waveform Counts:
Sensor: 245
Sampic: 245

Sensor Amplitudes:
Mean: -0.08
Std: 0.05
Max: -0.02

Sampic Amplitudes:
Mean: -0.41
Std: 0.07
Max: -0.22

Event Statistics:
Total events: 6401675
Sensor hits: 1132113
Sampic hits: 1129174
Coincidences: 245



Outlook

Summary

- **Sensor Design & Fabrication:**

- Simulation-driven R&D, optimization of column geometry, thickness, and isolation structures
- Double-sided and single-sided explored
- Focusing on single-sided *SINTEF*

- **Simulation Studies:**

- Parametrized TCAD models and Garfield++ simulations are in an advanced stage of development.
- Full automated simulation chain in works.

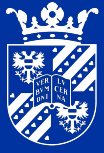
- **Characterisation and Campaigns:**

- IV/CV, laser, and source setups being commissioned
- Last test beam data (October 2025) expected to be good for some first results on 3Ds

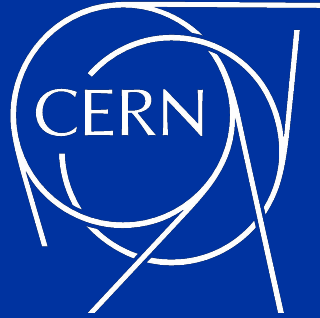
Outlook

Future Work

- **Simulation Pipeline Extension:**
 - Further parameter variation to drive R&D
 - Incorporate post-irradiation effects
 - Validate signal formation using Garfield++
- **Fabrication and Testing:**
 - Within 12-14 months, large and wide variety of samples to be characterized
- **Upcoming:**
 - Test Beam data analysis
 - Irradiated sensor characterization
- **Final Goal:**
 - Build a full chain from TCAD → Garfield++ → ... → experimental validation
 - Deliver practical sensor design recommendations for VELO Upgrade II and beyond



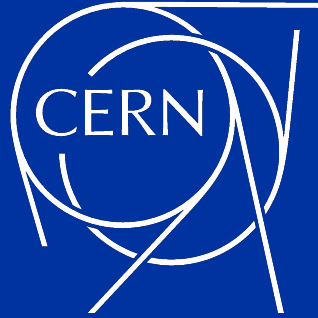
university of
 groningen



Thank you!



university of
 groningen



Backup slides

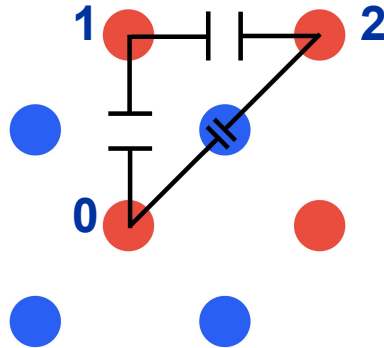
Backup

3D Sensor: Modelling and Approach

1E Geometry

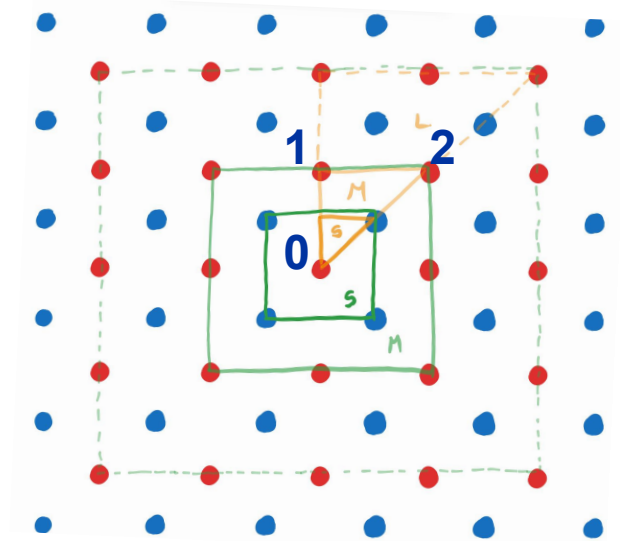


Interested in pixel behaviour *considering neighbors.*



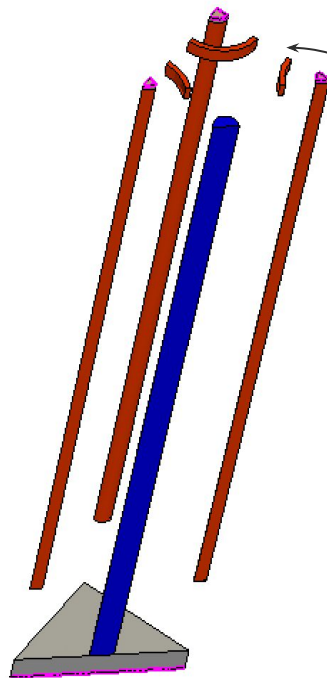
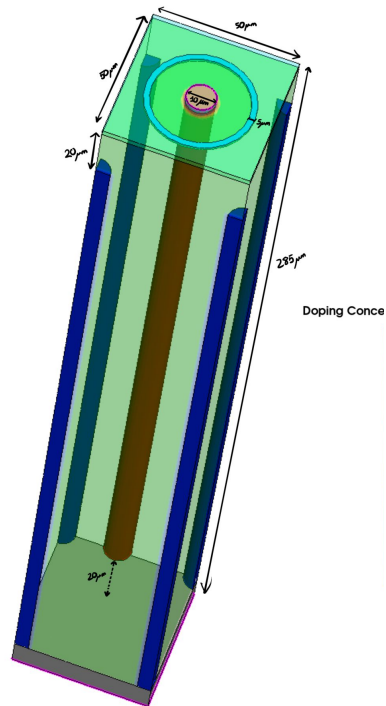
Constraints:

- Computational time is large
- Account for neighbor effects



Backup

3D Sensor: Double Sided (DS)



Characteristics: (Certain features of structure might be exaggerated for visualisation purposes)

- Columns come from **both** sides
- p-stop ring around n cols.
- Metal at the bottom to bias p col.

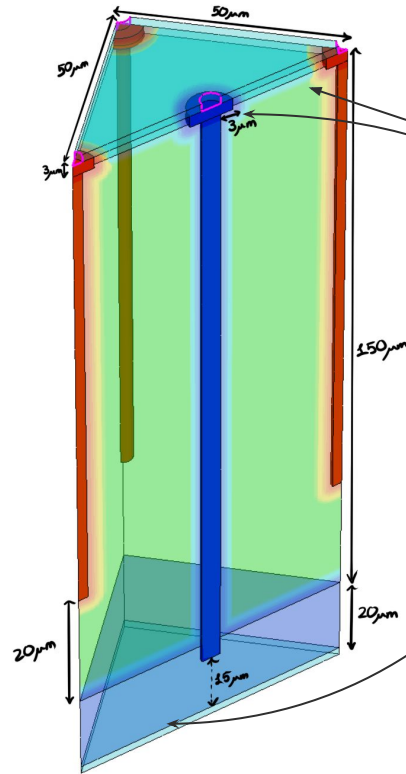
Difficulties:

- Acute angles and small areas for n cols.
- P-stop ring definition influences greatly.

The 3D sensor model was constructed following the CNM reference, with dimensions and features informed by the detailed specifications presented in Ò. Ferrer Naval's PhD thesis (Universitat Autònoma de Barcelona, 2024).

Backup

3D Sensor: One Sided - Single Sided (OS)



Characteristics: (Certain features of structure might be exaggerated for visualisation purposes)

- Columns come from **same** side p-spray covering surface.
- **N++** and p++ on top of cols.
- P++ region at the bottom to bias

Difficulties:

- Acute angles and small areas for n cols.
- P-spray definition influences greatly.

Backup

3D Sensor: Capacitance

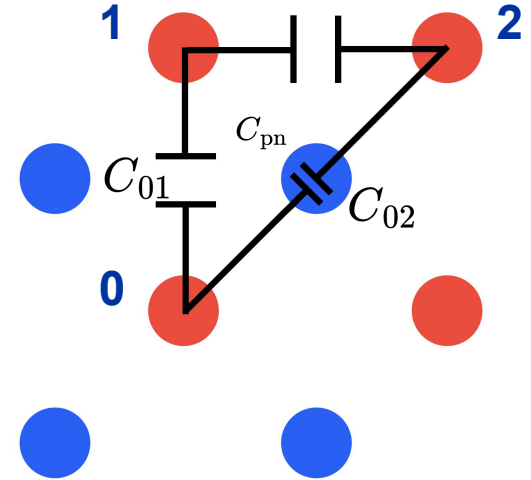
Contributions:

- C_{pn} = Bulk capacitance within the triangle
 - $C_{interpixel}$ = from neighbouring columns
- $$C_{interpixel} = C_{01} + C_{02}$$

$$C_{fullpixel} = 2C_{pn} + 4C_{interpixel}$$

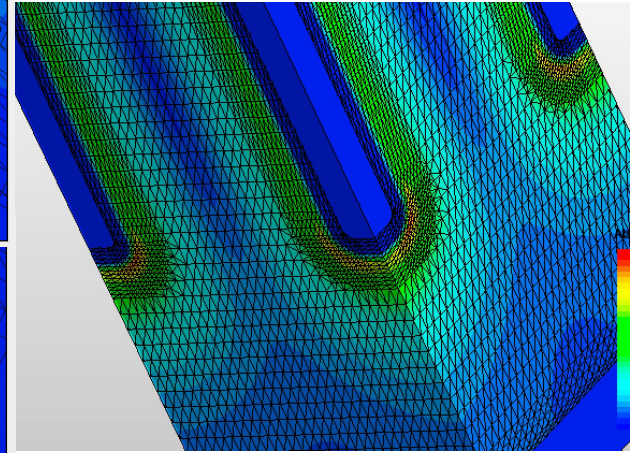
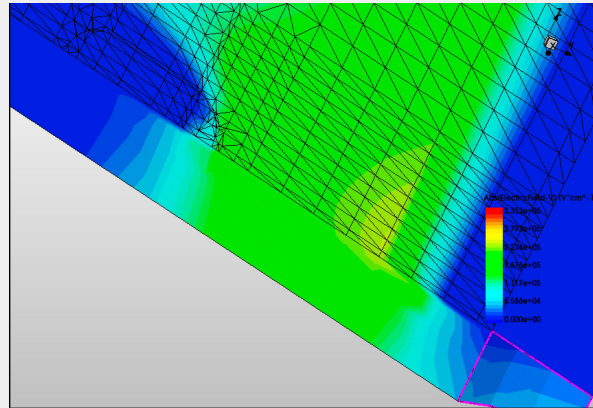
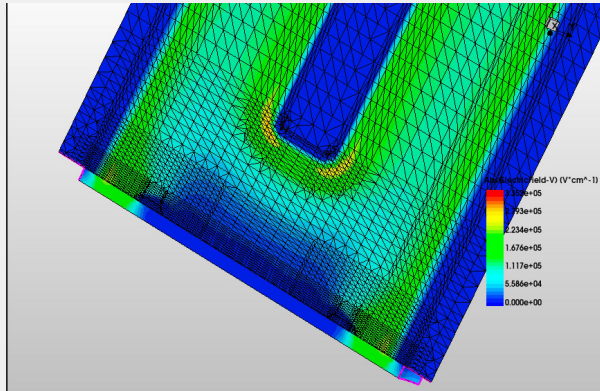
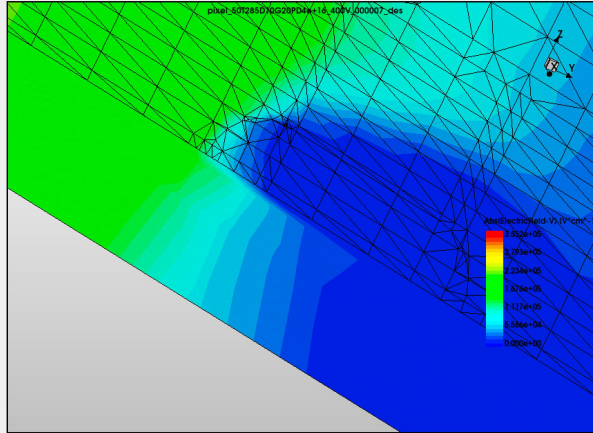
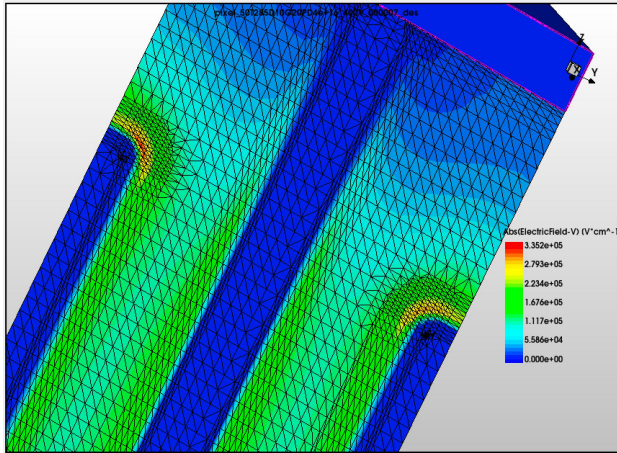
Final 1E pixel capacitance:

$$\begin{aligned} C_{fullpixel \text{ extra}} &= (2C_{pn} + 4C_{interpixel}) \times 1.2 \\ &= (2C_{pn} + 4C_{interpixel}) + 20 [fF] \end{aligned}$$



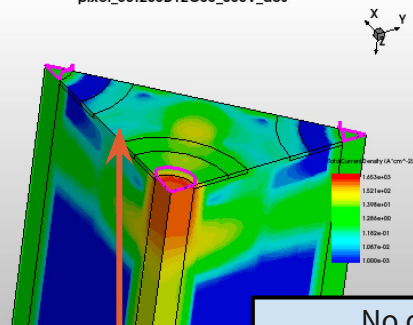
(Same papers state 20% extra contribution from geometry elements involved or approx 20fF)

Simulations: TCAD



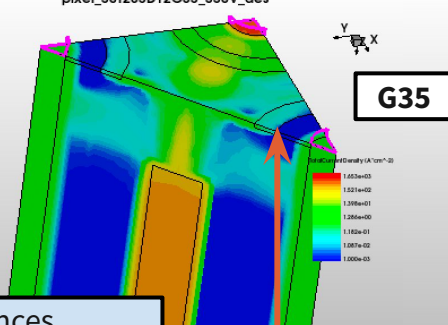
Double Sided: under n-column gap variation

pixel_50T285D12G35_350V_des



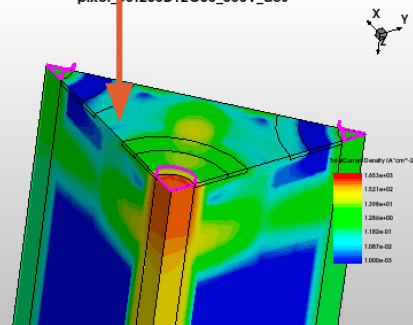
No differences
upper region

pixel 50T285D12G35 350V des

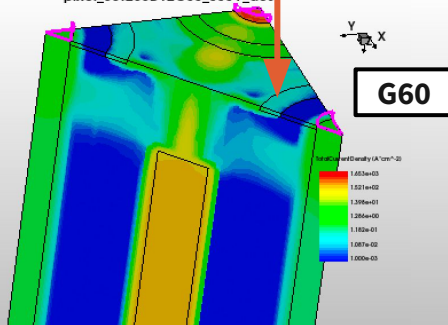


G35

pixel_50T285D12G60_350V_des

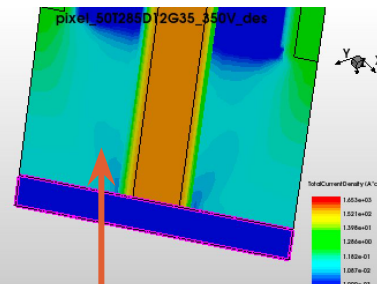


pixel_50T285D12G60_350V_des



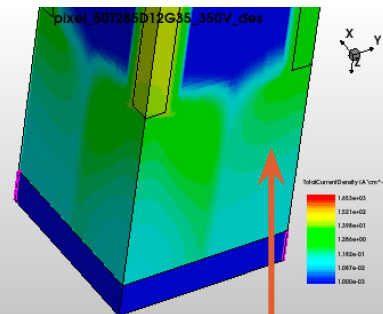
G60

pixel_50T285D12G35_350V_des



Obvious differences bottom region

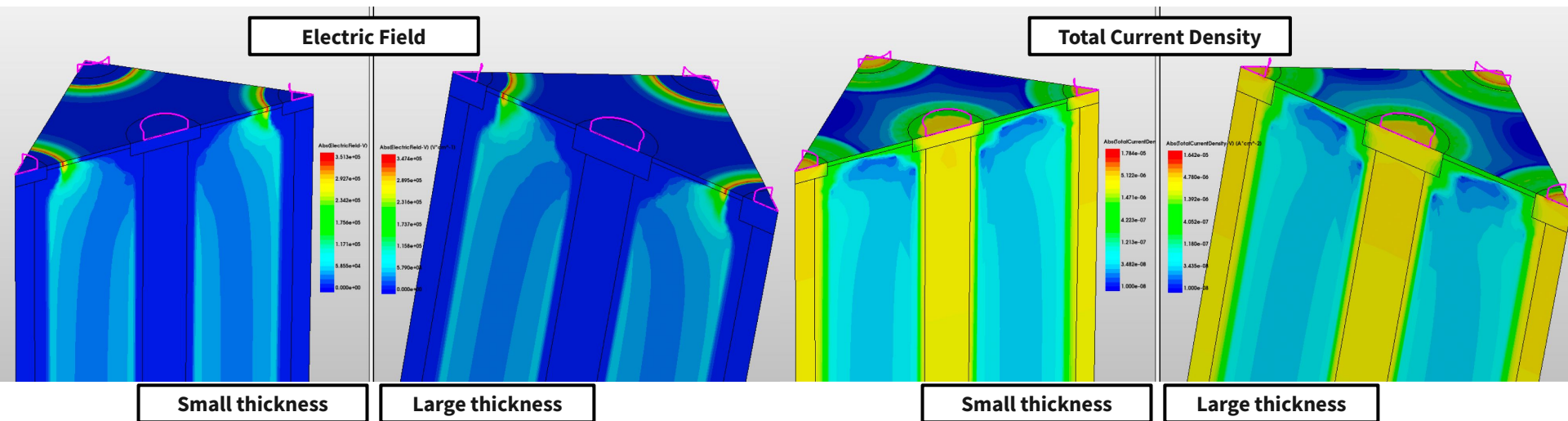
pixel 50T285D12G35 350V des



=> Breakdown occurs top of sensor <=

Simulations: Status and Plans

One Sided: n++ and p++ thickness



Preliminar Outcome:

For thicker n++ and p++ regions:

- Field lines spread more, not concentrating as strongly → lower chance of breakdown?

Disclaimer

The upcoming models and results are still under construction 🚧.

Handle with care — and patience.

Simulations: Status and Plans

One Sided: n++ and p++ extra radius

Study:

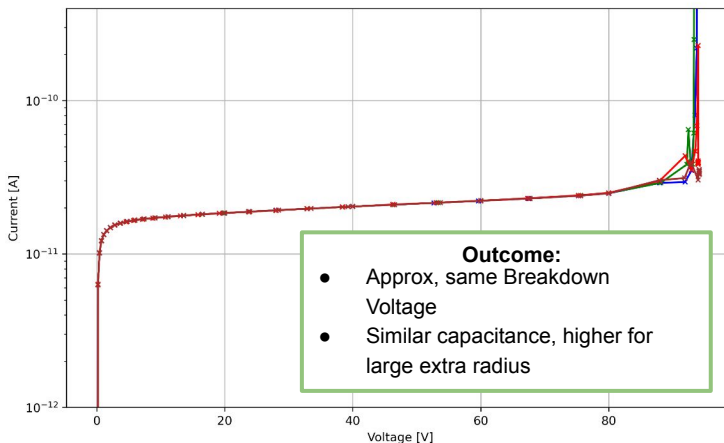
- Column diameter kept constant
- Variation of extra radius such that

$$R_{n++} = R_{p++}$$

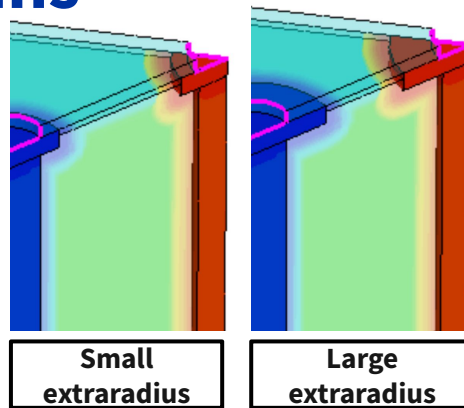
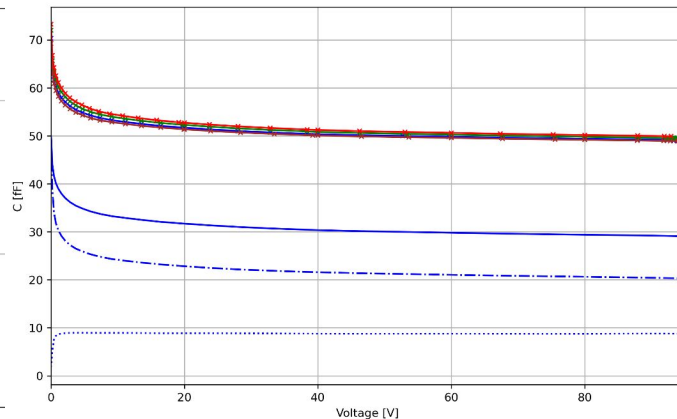
Aim:

- Influence on E field and breakdown

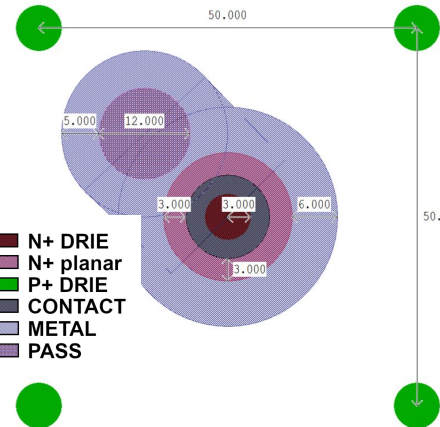
I vs V



C vs V



N+ DRIE
 N+ planar
 P+ DRIE
 CONTACT
 METAL
 PASS



M. Povoli et al., "Sintef Overview."

VELO U2 Workshop, CERN, Nov. 2024

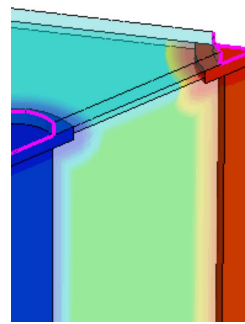
Geometry specifications:

- Pitch = 50 μm
- Thickness = 230 μm
- Gap p col., n col. = 0, 35 μm
- Diam. p col., n col. = 10.5, 9 μm
- $T_{p++} = T_{n++} = 3 \mu\text{m}$
- $R_{p++} = R_{n++} = [3, 4, 5.5, 6.5] \mu\text{m}$
- Pspray = 1 μm +diffusion, doping: 2e16

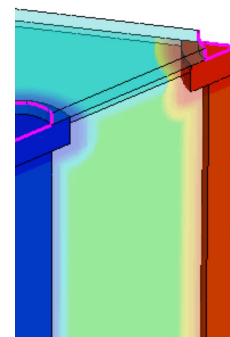
Simulations: Status and Plans

One Sided: n++ and p++ thickness

- **Study:**
 - P-spray thickness kept constant
 - Variation of thickness $T_{n++} = T_{p++}$
- **Aim:**
 - Influence on E field and breakdown

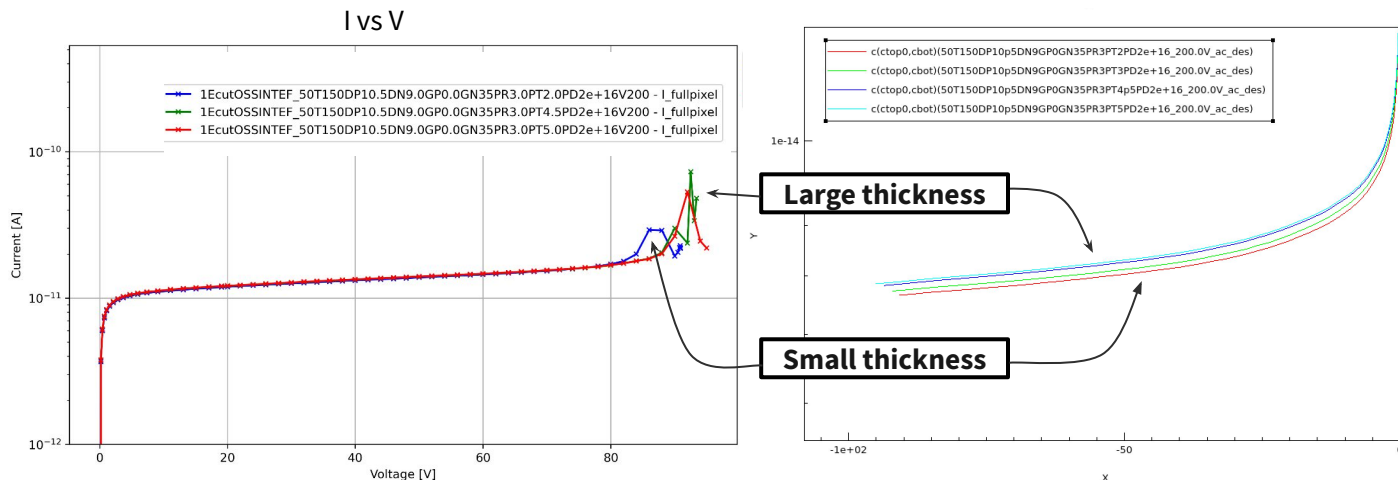


Small thickness



Large thickness

C vs V



Outcome:

- Slightly Different Breakdown Voltage
- Higher breakdown voltage and capacitance for larger thickness

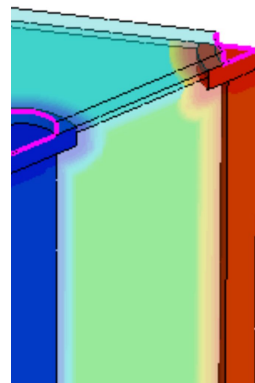
Geometry specifications:

- Pitch = 50 μm
- Thickness = 150 μm
- Gap p col., n col. = 0, 35 μm
- Diam. p col., n col. = 10.5, 9 μm
- $T_{p++} = T_{n++} = [2, 3, 4.5, 5] \mu\text{m}$
- $R_{p++} = R_{n++} = 3 \mu\text{m}$
- Pspray = 1 μm +diffusion, doping: 2e16

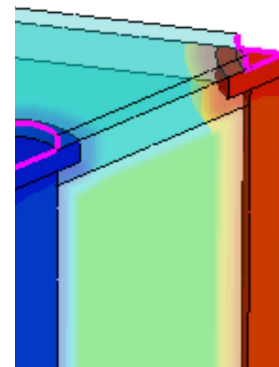
Simulations: Status and Plans

One Sided: p-spray thickness

- **Study:**
 - **n++** and **p++** thickness kept constant
 - P-spray thickness varied
- **Aim:**
 - Influence on E field and breakdown

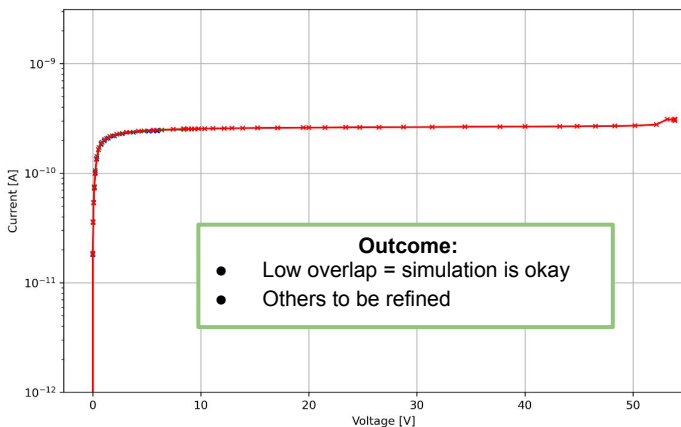


Small thickness

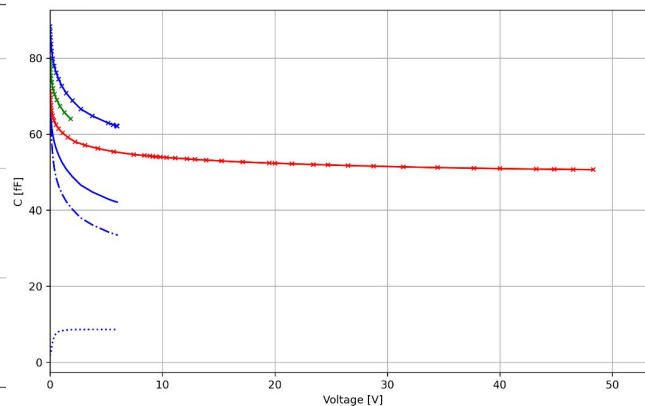


Large thickness

I vs V



C vs V



1EcutOS_50T230DP10.5DN9.0GPhanGN35PRnanPT5.0PD4e+16V200 - C_fullpixel (+20fF extra)
 1EcutOS_50T230DP10.5DN9.0GPhanGN35PRnanPT5.0PD4e+16V200 - C_fullpixel
 1EcutOS_50T230DP10.5DN9.0GPhanGN35PRnanPT5.0PD4e+16V200 - C_pn_pixel
 1EcutOS_50T230DP10.5DN9.0GPhanGN35PRnanPT5.0PD4e+16V200 - C_interpixel
 1EcutOS_50T230DP10.5DN9.0GPhanGN35PRnanPT3.0PD4e+16V200 - C_fullpixel (+20fF extra)
 1EcutOS_50T230DP10.5DN9.0GPhanGN35PRnanPT1.0PD4e+16V200 - C_fullpixel (+20fF extra)

Geometry specifications:

- Pitch = 50 μm
- Thickness = 150 μm
- Gap **p col.**, **n col.** = 0, 35 μm
- Diam. **p col.**, **n col.** = 10.5, 9 μm
- **T_{p++}** = **T_{n++}** = 3 μm
- **R_{p++}** = **R_{n++}** = 3 μm
- Pspray = [1, 3, 5] μm +diffusion, doping: 4e16

Simulations: TCAD

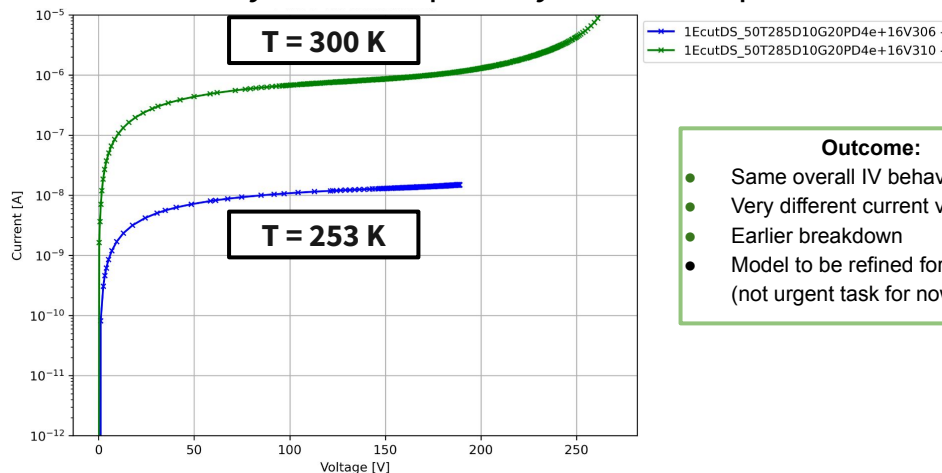
Double Sided: Temperature variation

- **Study:**

- Influence of temperature on simulation
 - Previous simulations with 300K (27°C)
 - Changed to 253K (-20°C)

- **Aim:**

- Test physics models and math solvers used in simulation
- Verify model capability at low temperatures for future studies



Outcome:

- Same overall IV behaviour
- Very different current value
- Earlier breakdown
- Model to be refined for low T (not urgent task for now)

- **To be improved...**

- Test with One Sided
- Modify temperature dependent physics models considered

Simulations: Status and Plans

Future

- **TCAD:**

- Single/One Sided:
 - *Refine model with feedback from SINTEF*
 - *Complete the ongoing studies presented here*
- Double Sided:
 - *Refine model to then compare simulations to characterization*
- Common among models:
 - *Further improve meshing to account for all possible parameter variations, surface effects...*
 - *Incorporate radiation damage effects*
 - *Enhancing modeling at low temperatures (not critical for now)*

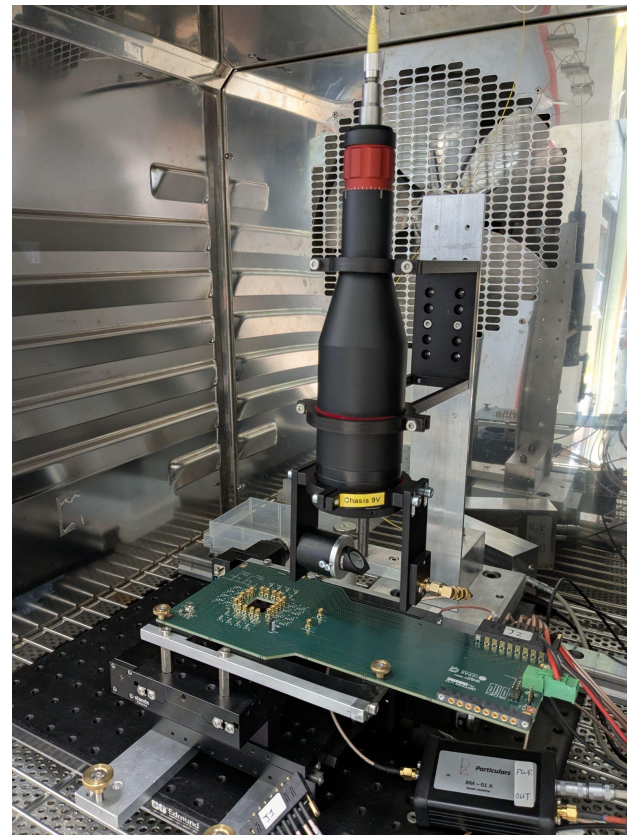
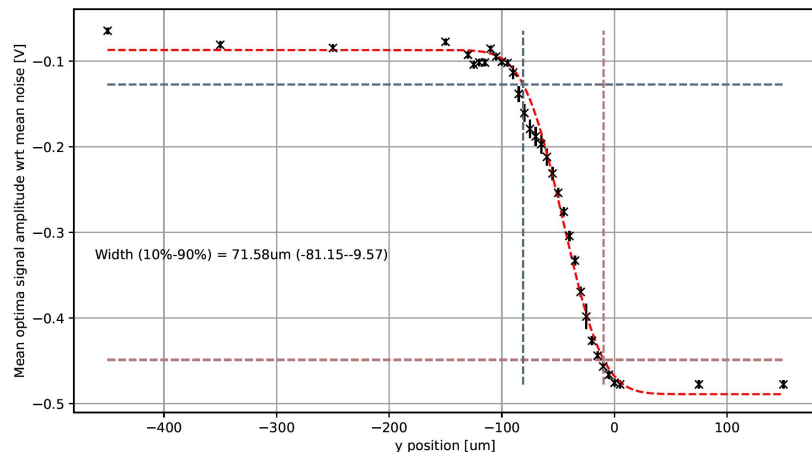
- **Simulation chain:**

- Completion of Garfield ++
 - *Perform charge transport and signal induction modeling with Garfield++*
 - *Conduct semi-manual analysis of simulation output data*
- *Begin with Analog Front End implementation*

Characterisation

Setups

- **Laser (660 nm & 1064 nm) system**
- **Set-up for source and laser tests** of samples using OPTIMA within sealed environment
- **Envisage calibration, in-pixel mapping, time resolution measurements**
- **Currently under commissioning:** focussing measurements for different DUT positions



Many thanks to Leena Diehl, Raphael Dumps, and Stephane Detraz

Characterisation

Test Beam July 2025

- **Some plots from operation:**

- Spatial alignment of samples with the beam
- Time alignment of tracks on Telescope and hits on sample

